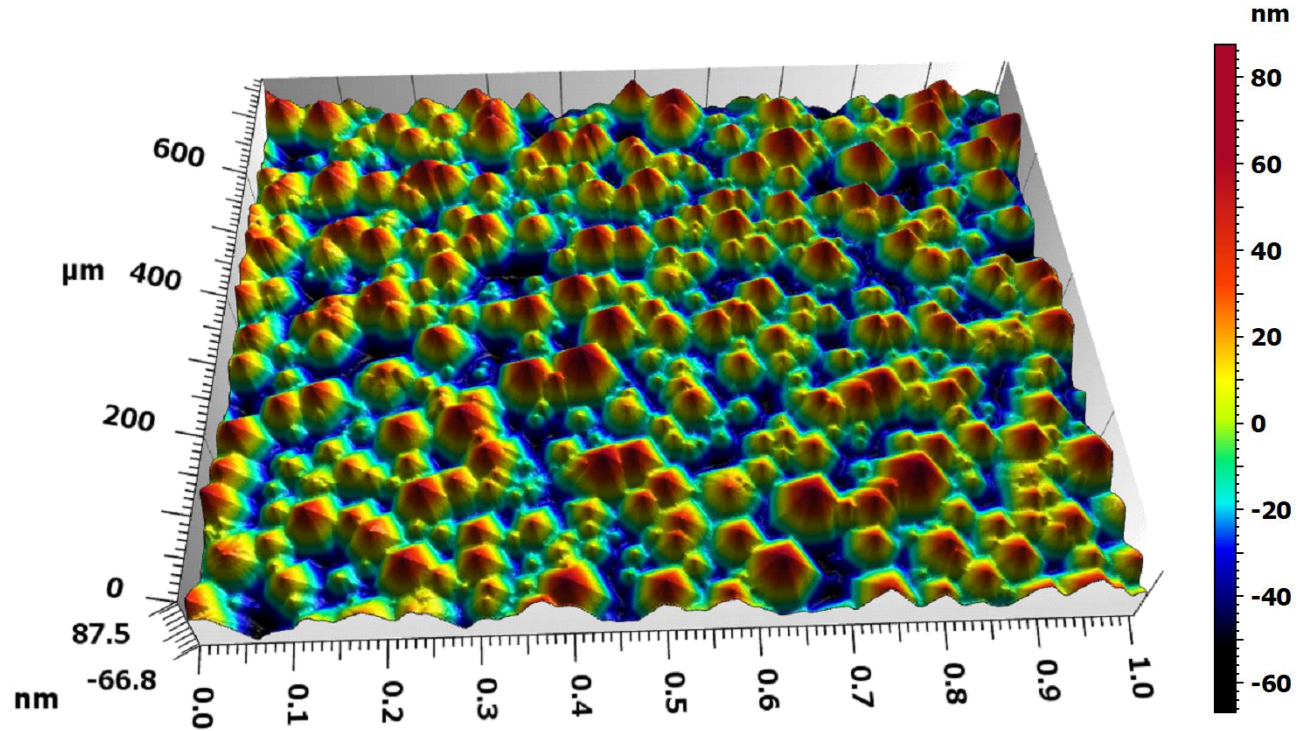


optical measurement of functional surfaces



with super resolution

short introduction of the GBS

**founded 1997 as a subsidiary of the ZBS
with roots in university research**

**quality assurance systems
based on massively parallel image processing**

**2008 installation of the first smartWLI
(high performance white-light interferometer)**

**focus on the smartWLI measuring devices Germany,
USA, Japan, France, China, Korea, Taiwan, Sweden,
UK, Switzerland, Israel, Austria, Spain, Norway, Italy...**



head quarter



company extension in 2019

GBS – continuous product development



2008



2009



2010



2011



2012



2013



2014



2015



2016



2017



2018



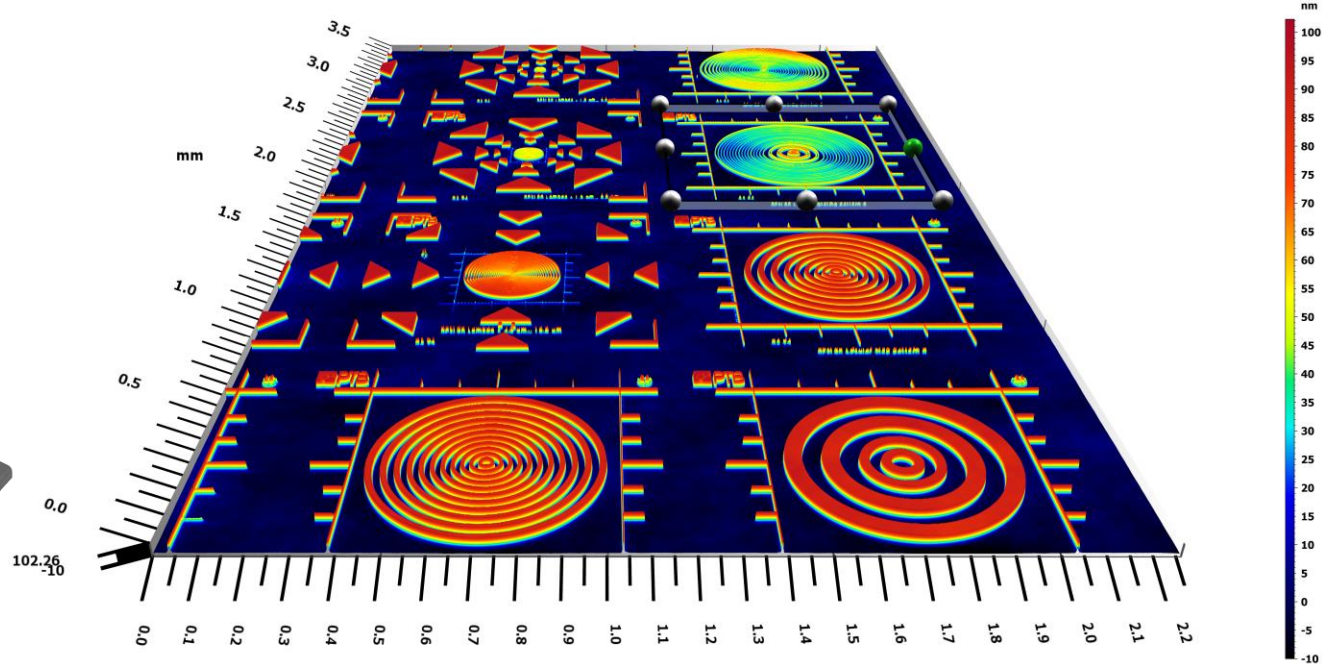
2019



smartWLI next – now available since June 2020!

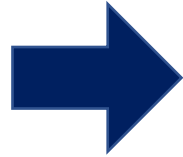


*universal lab measuring system
with up to 4 objectives and motorized turret*



massively parallel data processing

high resolution camera



more than 10 TFLOPS with 3,000 cores

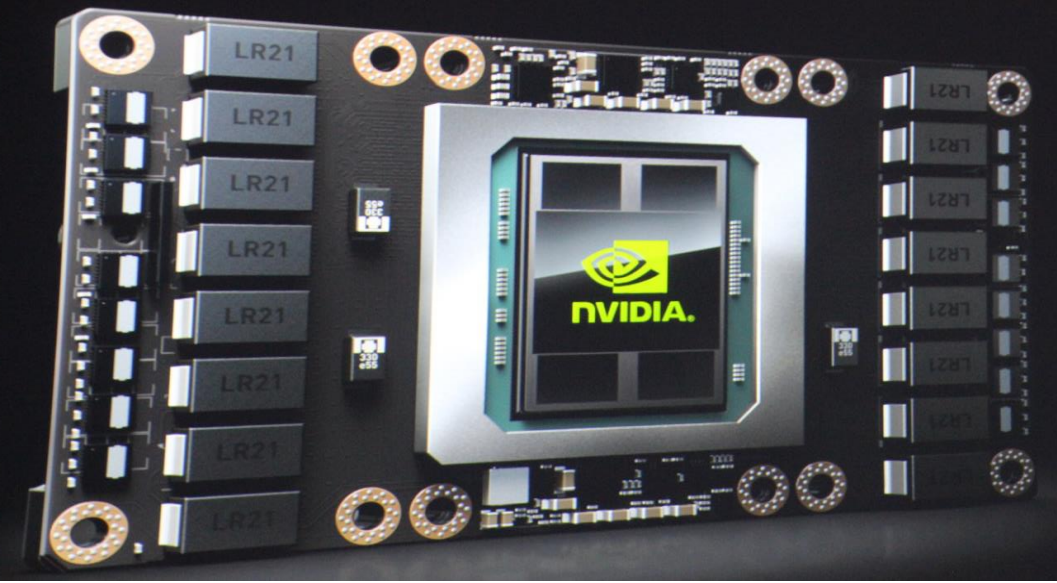
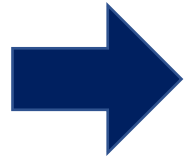
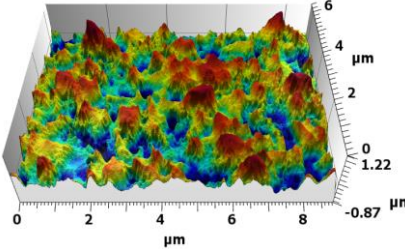


image correction, contrast enhancement
3D calculation in real time!

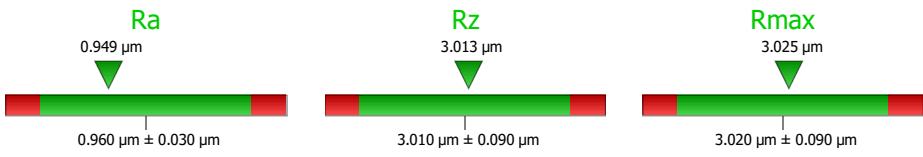
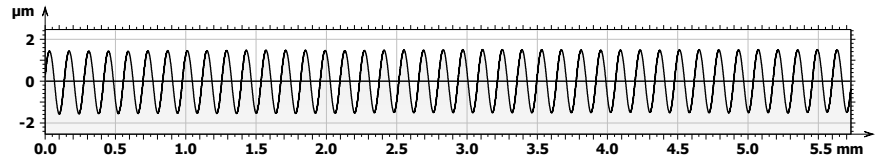
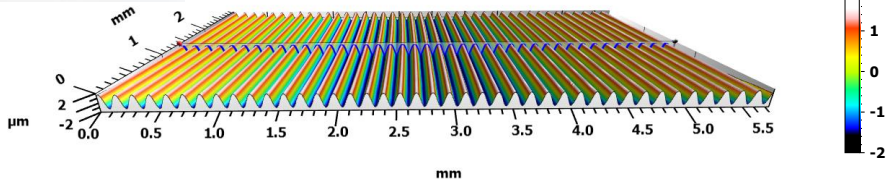


high resolution 3d data

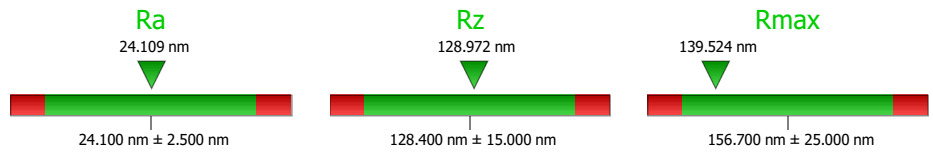
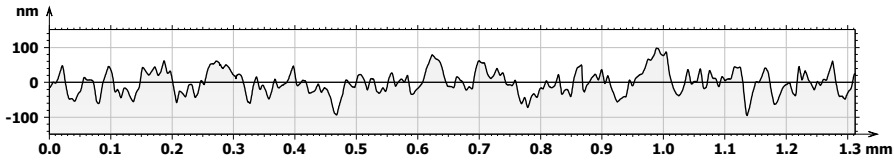
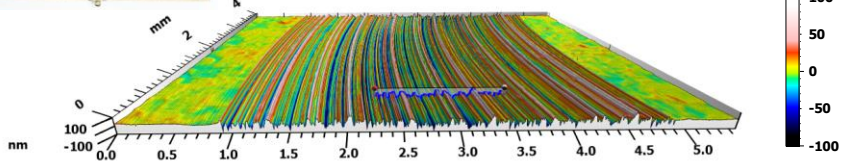


tracible surface roughness standards

**Mahr MSS-3
certified surface and step standard**

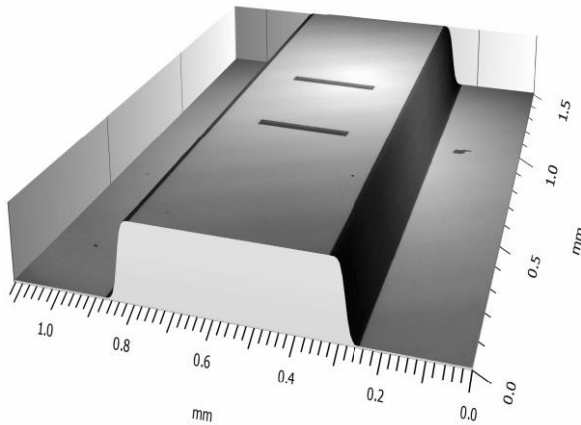


**Halle – super fine
certified surface roughness standard**



deviation smaller 30 nm / 100 μm step height

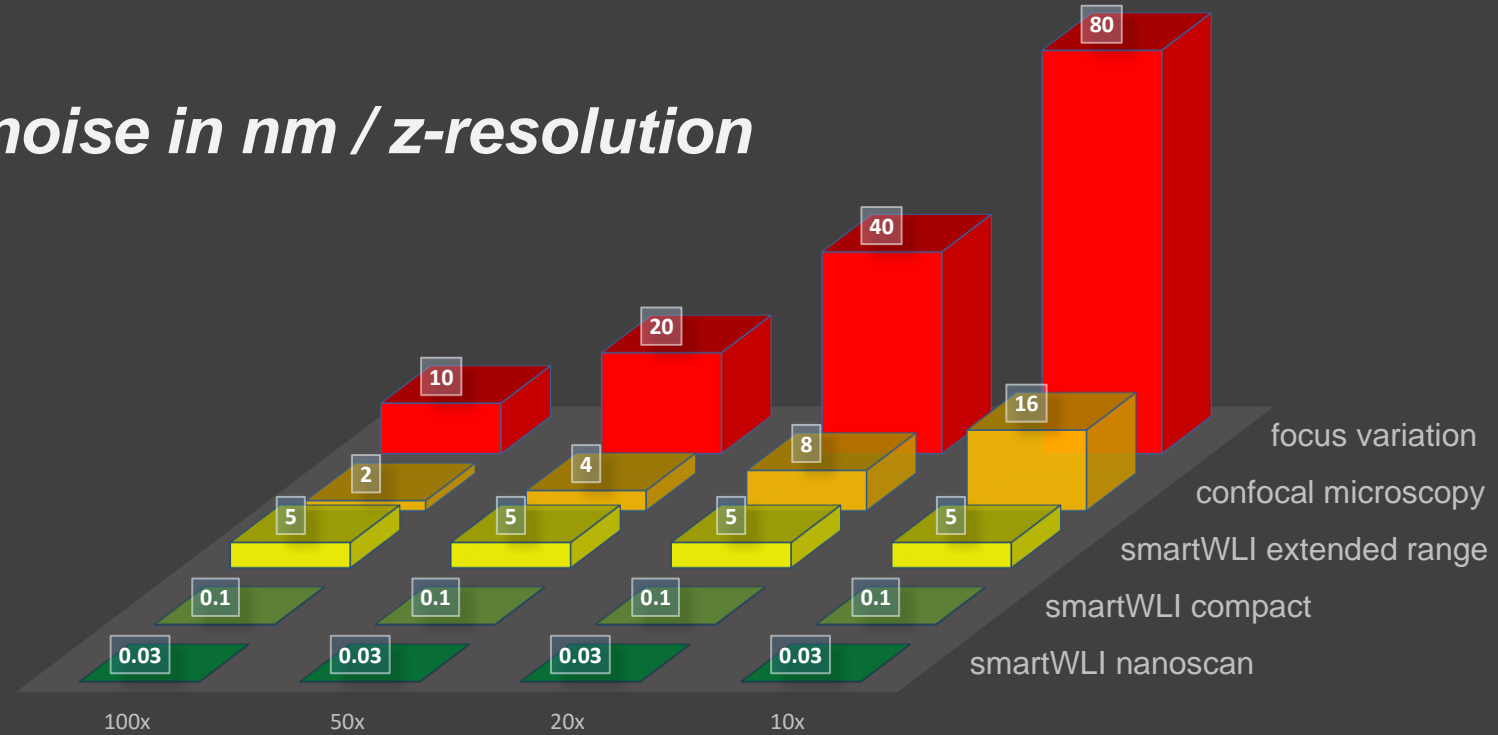
SiMetricS – step height standard
optional with PTB - Zertifikat



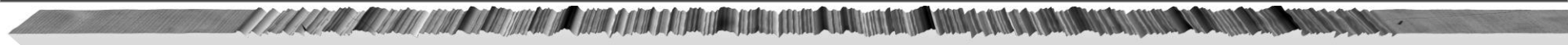
Factory Calibration Certificate			
System:		smartWLI compact	
Objective:		Nikon CF IC EPI Plan DI 10xA MUL40101	
Feature:		100μm Depth Standard	Pt / μm
Standard:		SiMetricS Serial Type A1	
Nominal Value / μm:		100.07	Uncertainty / ± μm: 0.030
Nr.	Pt / μm	<p>100μm Depth Standard Pt / μm</p>	
1	100.0968		
2	100.0844		
3	100.0807		
4	100.0941		
5	100.0862		
6	100.0949		
7	100.0823		
8	100.0908		
9	100.0905		
10	100.0860		
11	100.0866		
12	100.0903		
13	100.0888		
14	100.0886		
15	100.0891		
16	100.0877		
17	100.0865		
18	100.0887		
19	100.0865		
20	100.0767		
21	100.0752		
22	100.0844		
23	100.0850		
24	100.0913		
25	100.0911		
Min:	100.0752	System Deviation / μm:	0.017
Max:	100.0968	Reproducibility 1-σ / μm:	0.005
		Date	xxx
		Inspector	n.n

comparison to optical measuring principles

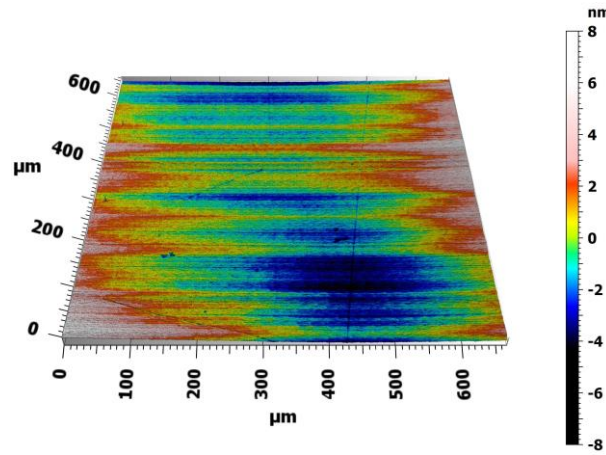
noise in nm / z-resolution



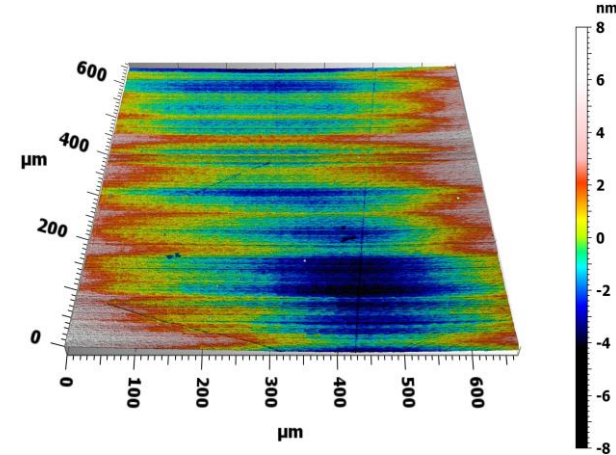
- *the smartWLI nanoscan provide a sub-atomic height resolution*
- *the improvement of the lateral resolution is very important*



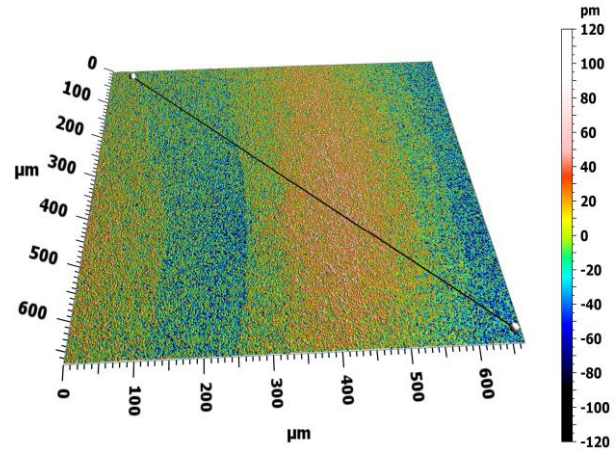
ISO 25178-604 2.1.11 system noise / single scan



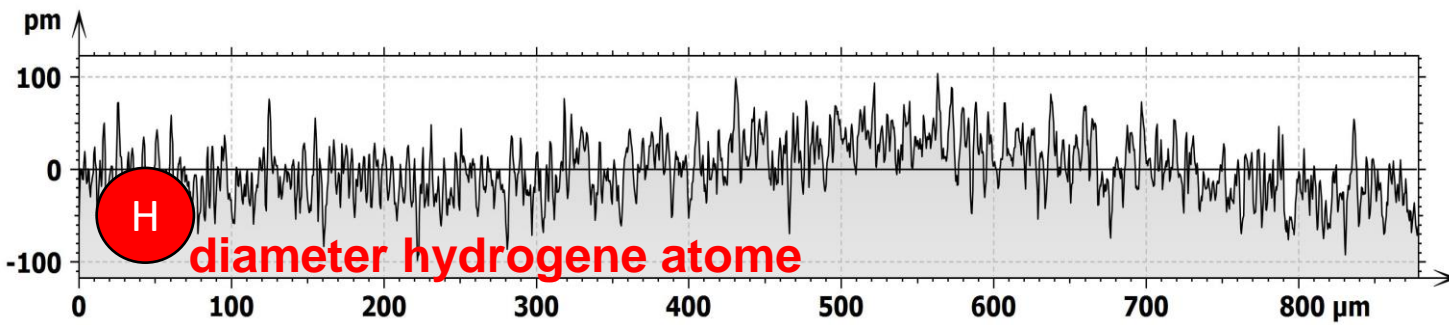
scan 1



scan 2



difference 1 - 2



ISO 25178 - Primary surface	
F:	None
As Filter:	No As-filtering
Height parameters	
Sq	33.9 pm
Sa	27.2 pm

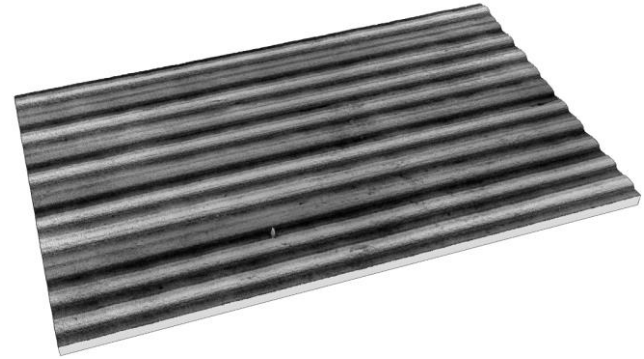


laser structuring for automotive application

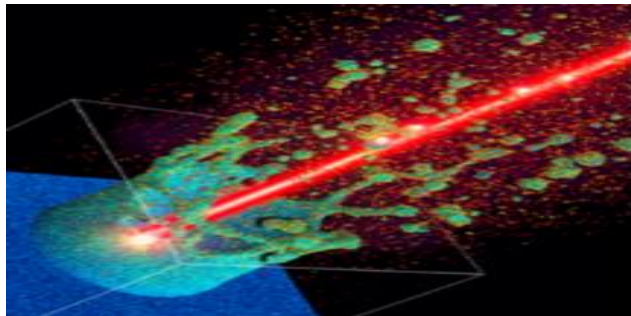
connecting rod



original surface



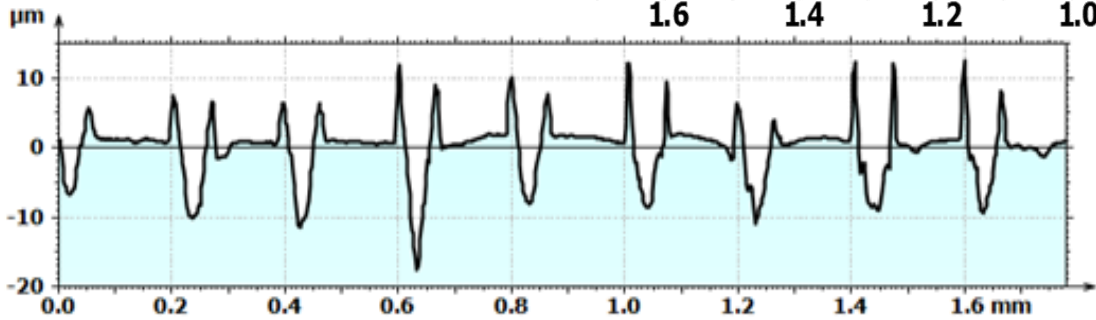
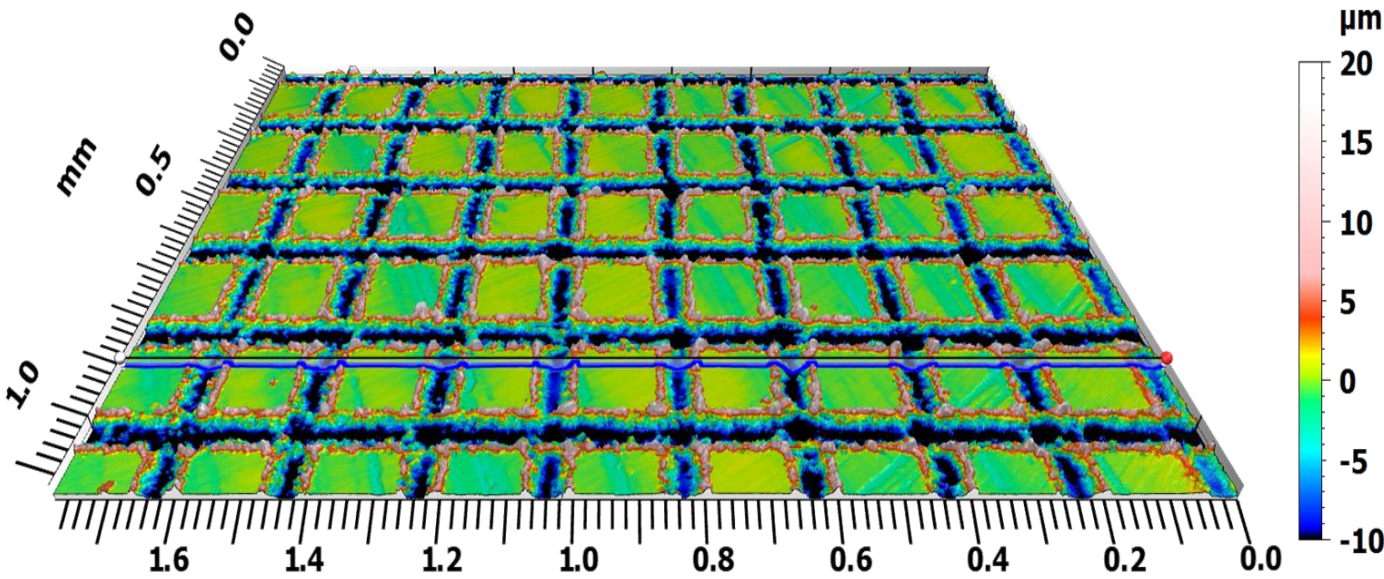
laser structuring



after laser structuring

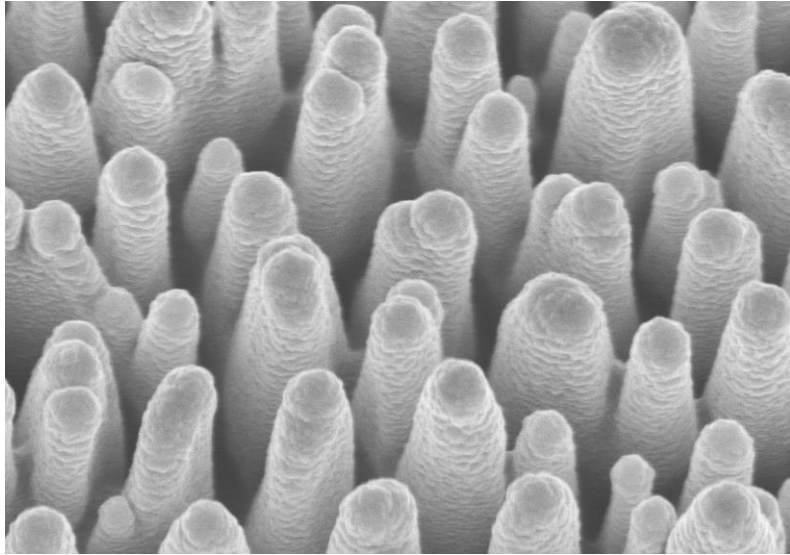


surfaces with defined functions



The laser grate increase the friction and enable the reduction of the friction area as well as the complete part.





SEM image
functional “black silicon” structure

AFM:

- structures could not be reached
- and potentially break the tip

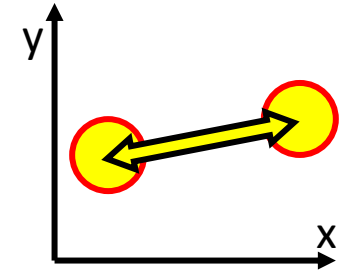
SEM stereoscopic reconstruction:

- getting pictures of the same spot with different slopes is difficult
- the aspect ratio allowed limited slope variations which limits the z-resolution
- the necessary autocorrelation reduce the lateral resolution significant

smartWLI:

- is it possible to measure such structures?
- what are the smallest structures which can be measured?

aperture and optical resolution for 2d pictures



Rayleigh – criterion light intensity has to drop of 73.5 % of the max. intensities

$$d = \frac{0.61 * \lambda}{NA}$$

d – distance between the light sources
 λ – wavelength of the light source
NA – numerical aperture of the objective

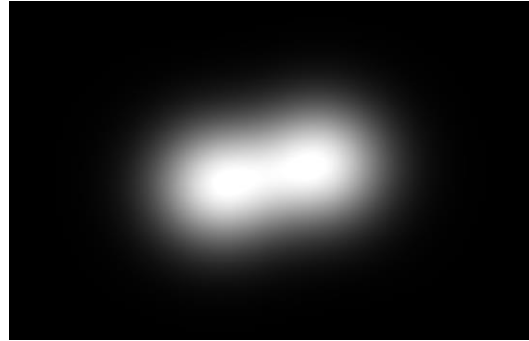
Sparrow's – criterion light intensity doesn't drop between max. intensities

$$d = \frac{0.47 * \lambda}{NA}$$

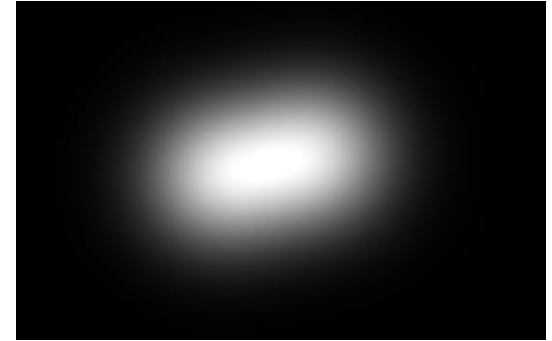
d – distance between the light sources
 λ – wavelength of the light source
NA – numerical aperture of the objective



separation possible

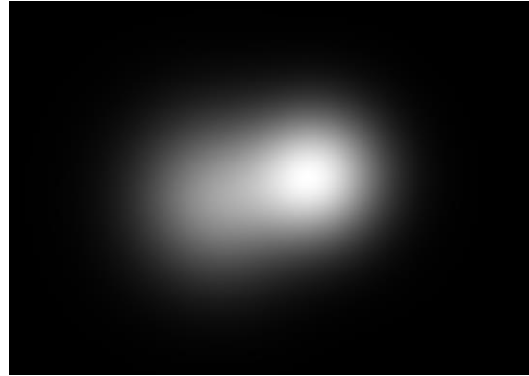
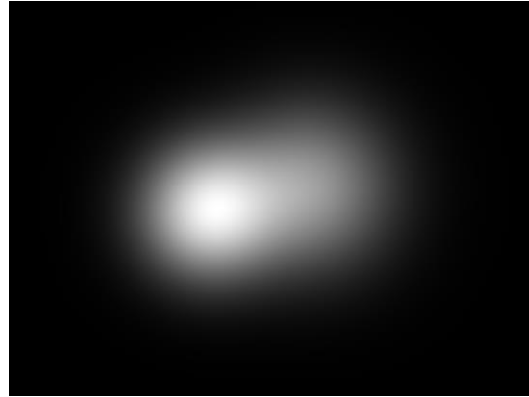
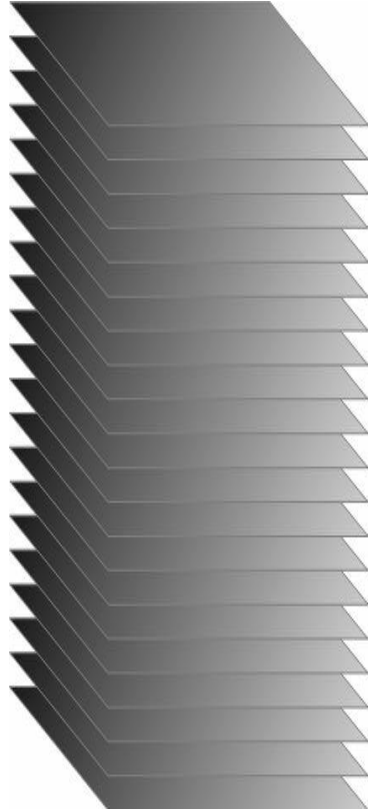
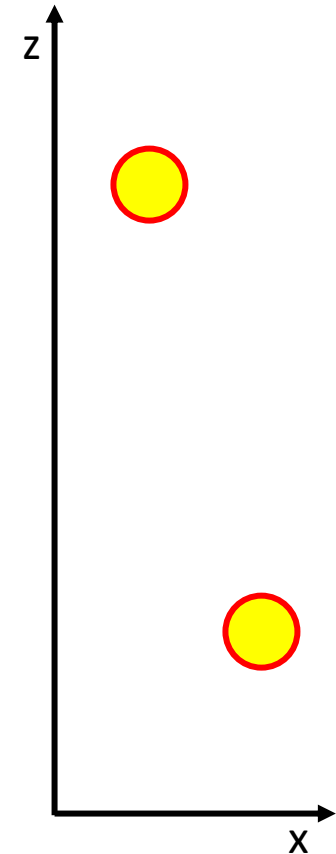


separation limit



separation impossible

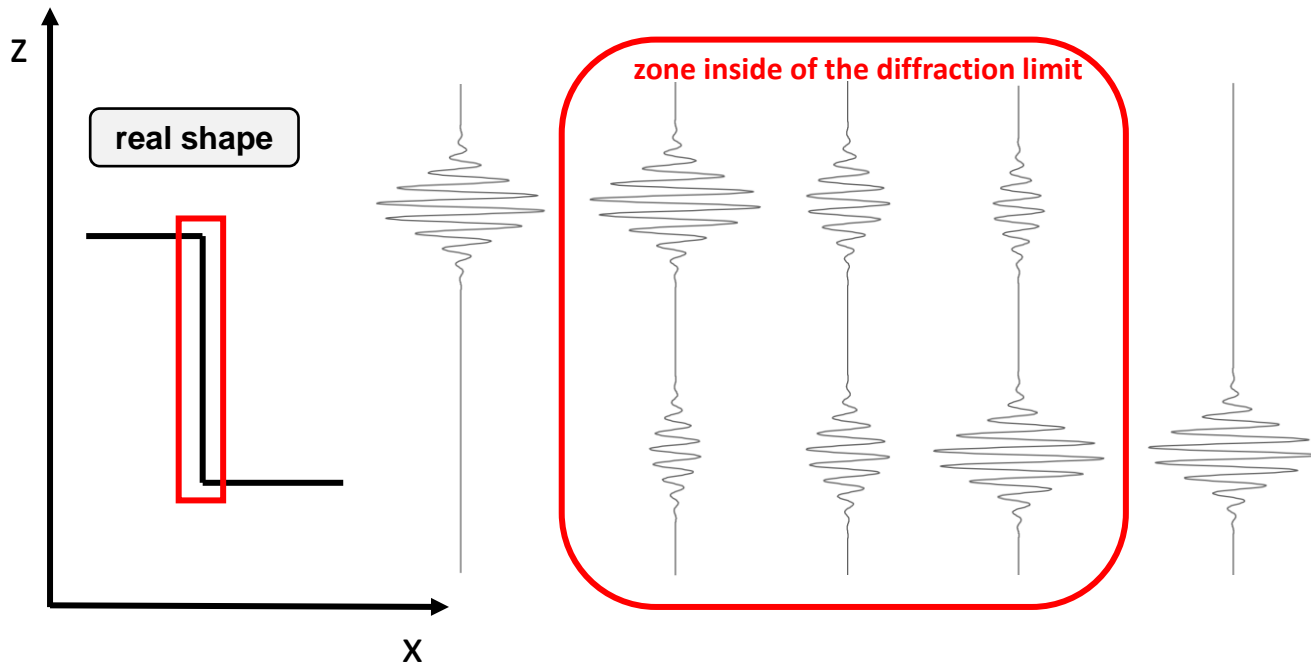
3d scanning, distance below optical resolution



- height differences simplify the signal separation
- the light source in optimal sharpness can better separated from the other light source at a different height level
- aperture and optical resolution still have a big influence on the system resolution of optical area scanning systems but based on the evaluation of image stacks the limit depends from the height differences of the structures
- instead of an optical image of both light sources at the same height level the separation is possible

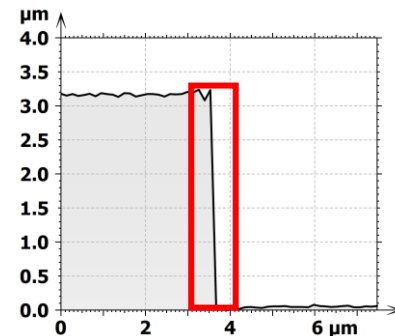


interferometric signal on a step

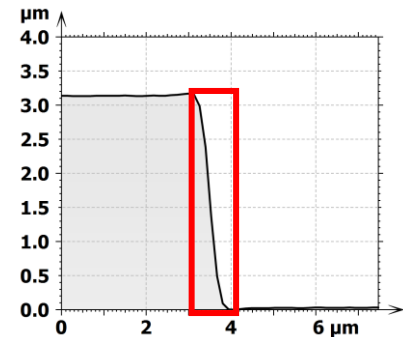


- the diffraction limit is the reason of an mixed signal of upper and lower level
- interferometry isn't based on the light intensity and advanced algorithms can separate both signals depending on the height differences, hardware components and used algorithm

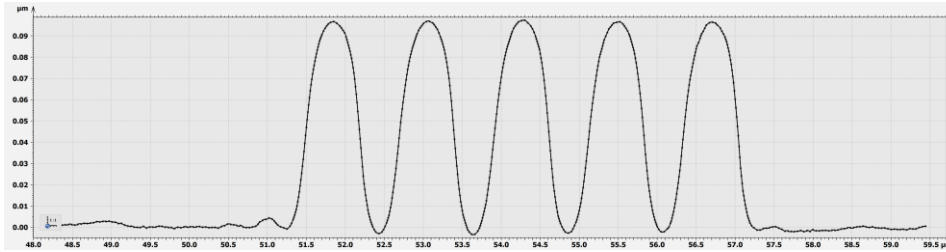
measuring result with
advances algorithm



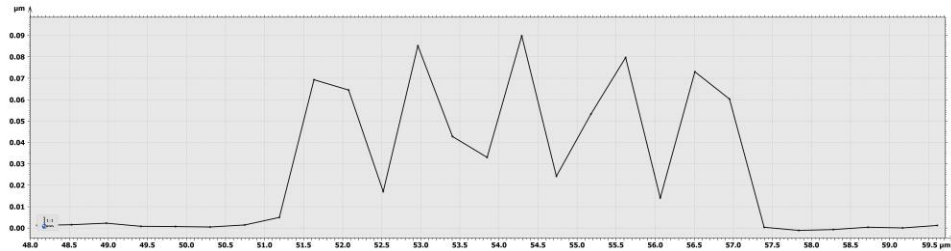
measuring result with
simple algorithm



ISO 25178-604 2.1.17 – D_{LIM} for objective tests

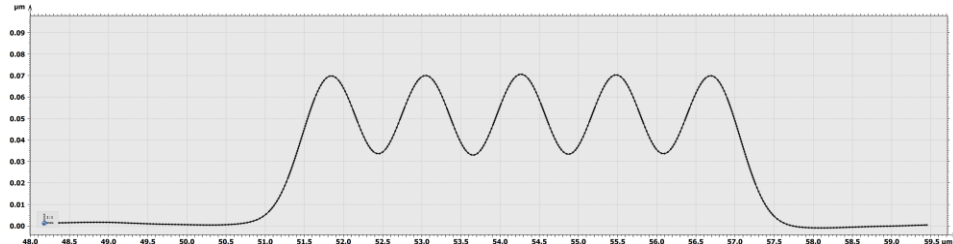


*sufficient point density
sufficient system
resolution*



insufficient point density

(amplitude below 50% of the real structure)



insufficient system resolution

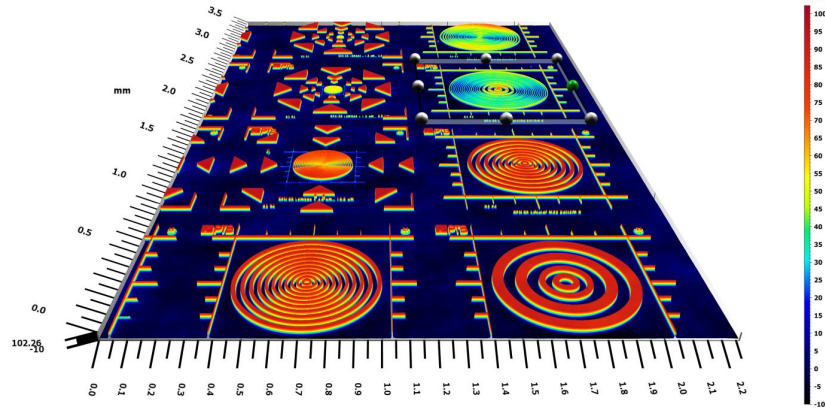
(amplitude below 50% of the real structure)

- *ISO 25178 specifies the scale limitations for the surface texture by areal methods*
- *the lateral period limit D_{LIM} is the spatial period of a sinusoidal profile at which the measured height falls to 50% of the real height*

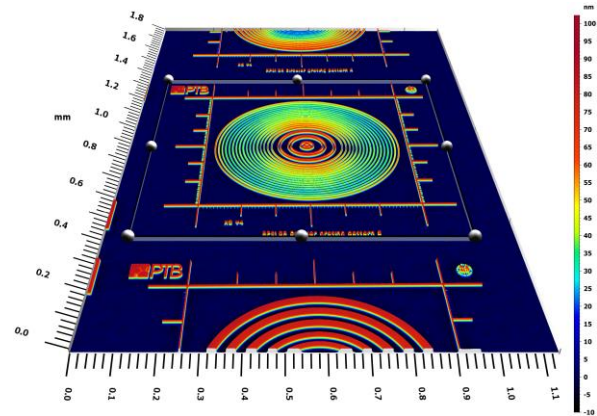


target with sinus structures for resolution tests

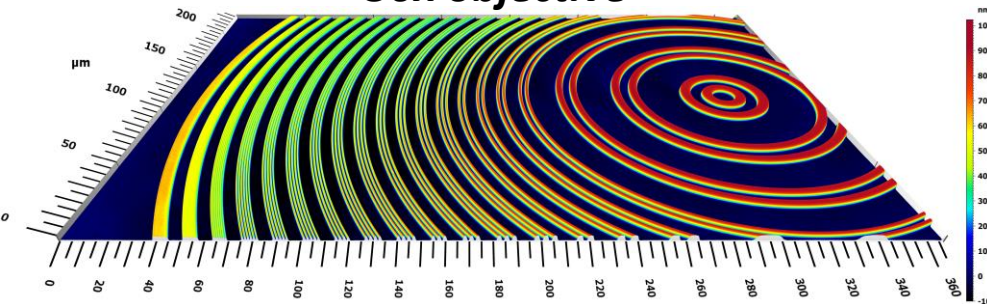
5x objective



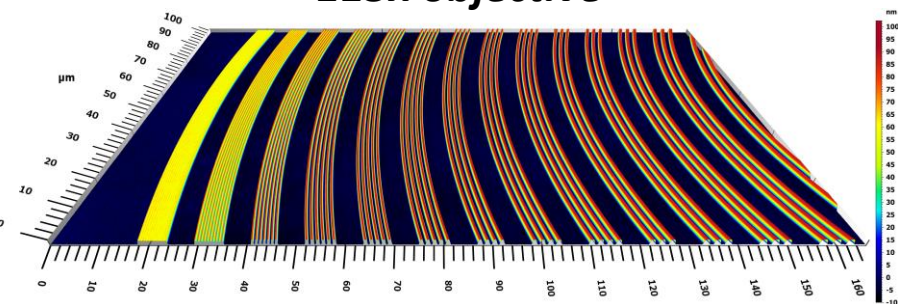
10x objective



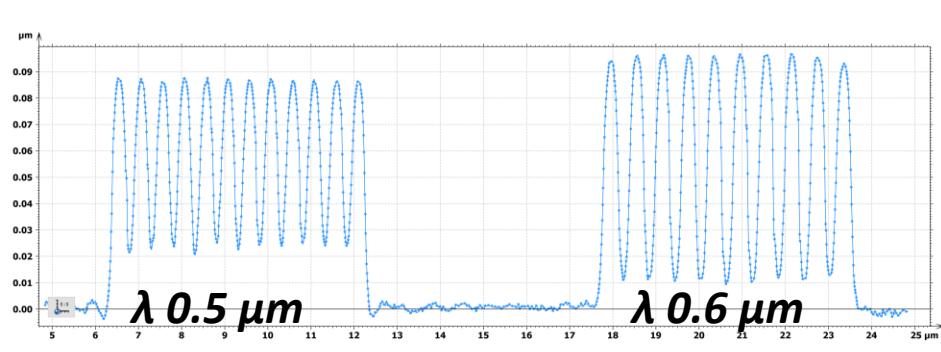
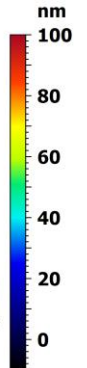
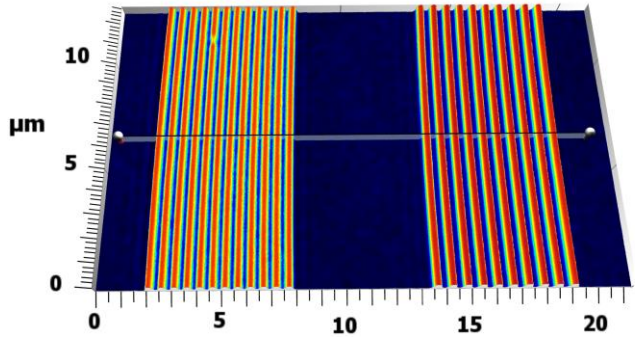
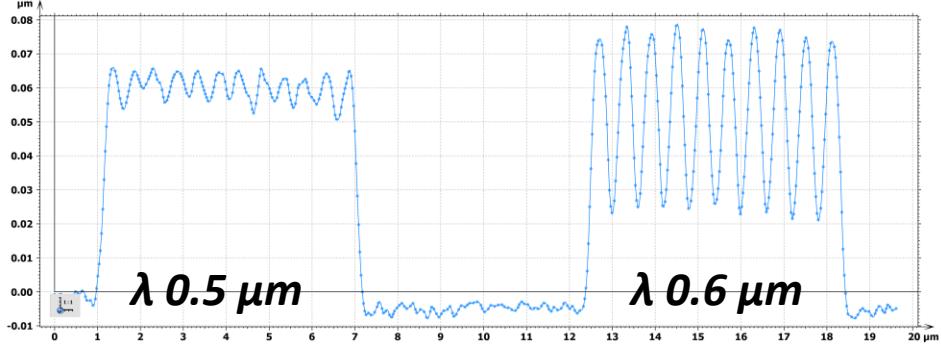
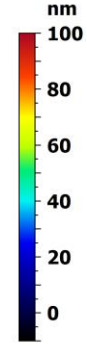
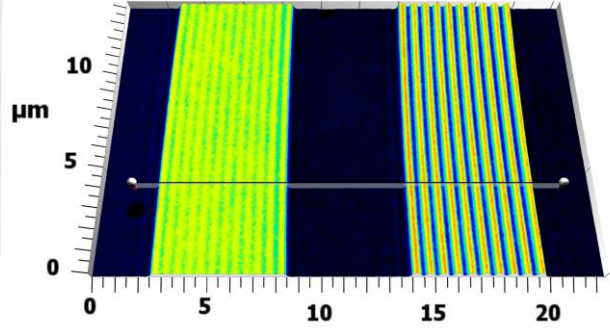
50x objective



115x objective



smartWLI nanoscan for highest resolution



The analysis proves that smartWLI nanoscan has not only a much better point density but also a 50% higher system resolution: D_{LIM} smartWLI compact 115x app. $0.6 \mu\text{m}$ / D_{LIM} smartWLI nanoscan 115x app. $0.4 \mu\text{m}$.



comparison of data processing strategies

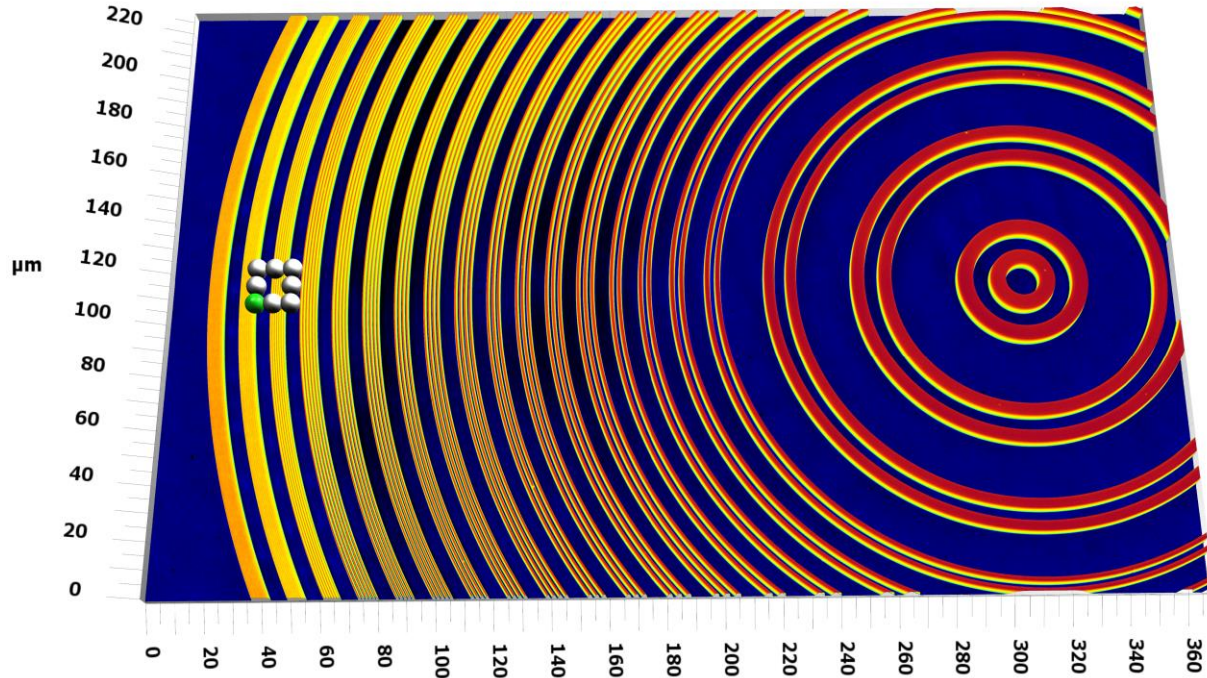
PTB resolution target, sinus structures with a wavelength of app. $0.8\ \mu\text{m}$ and an height of app. $0.08 \dots 0.1\ \mu\text{m}$

50x objective, point density $0.19\ \mu\text{m}$, optical resolution app. $0.6\ \mu\text{m}$, partial area out of $0.34 \times 0.28\ \text{mm}^2$

The point density is already far below the resolution limit. Can I really use filters to reduce the noise without losing significant height information?

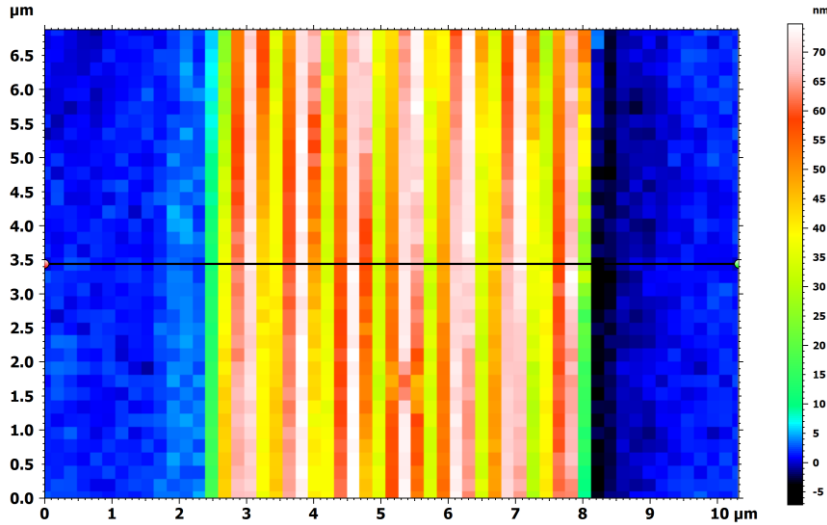
Is it possible to reduce the noise with phase averaging?

Is it possible to get better results with super resolution algorithms?

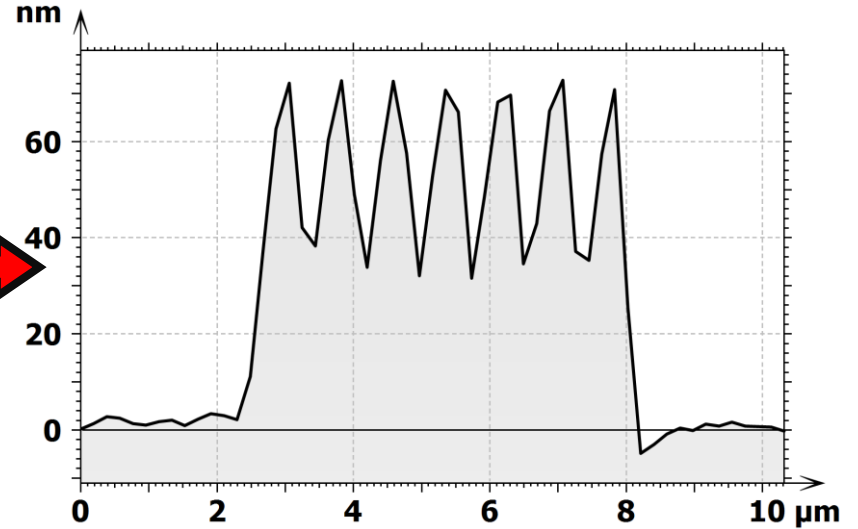


can the data processing be improved?

color coded 3d plot



profile



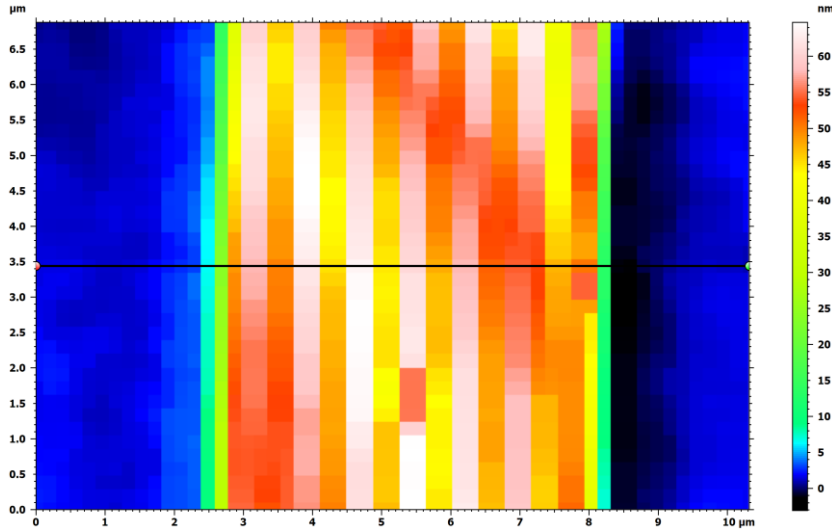
unfiltered raw data

modulation below 50% of the real structure height



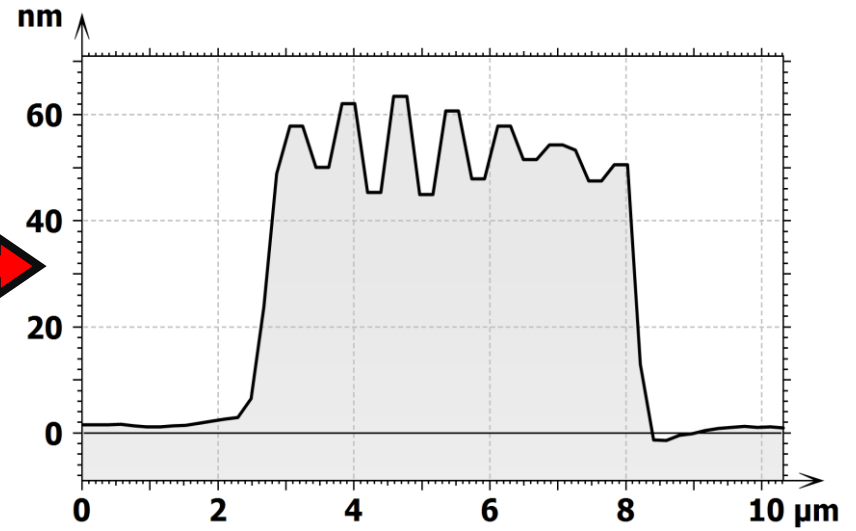
profile averaging, 3x3 median filter

color coded 3d plot



strong noise reduction

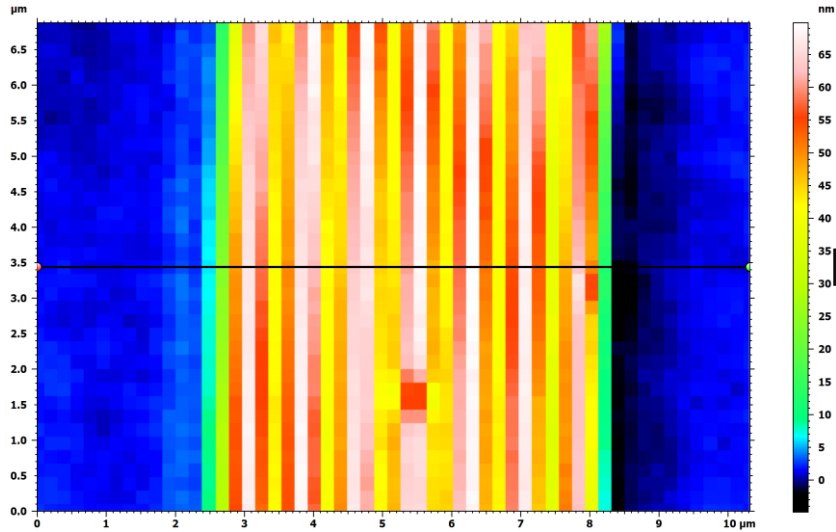
profile



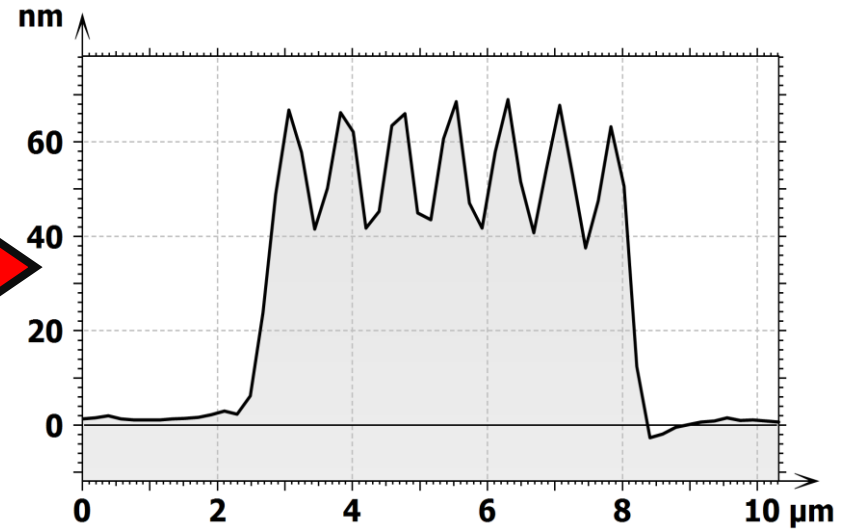
strong reduction of the height signal



color coded 3d plot



profile



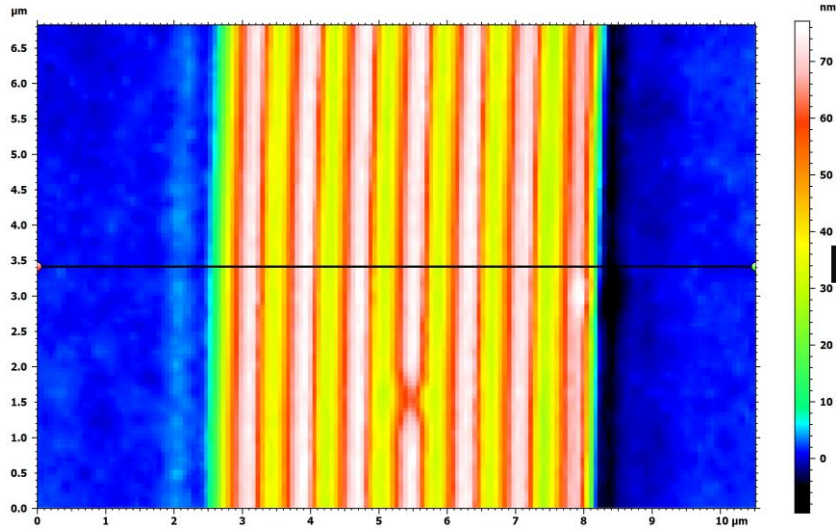
noise reduction

reduction of the height signal



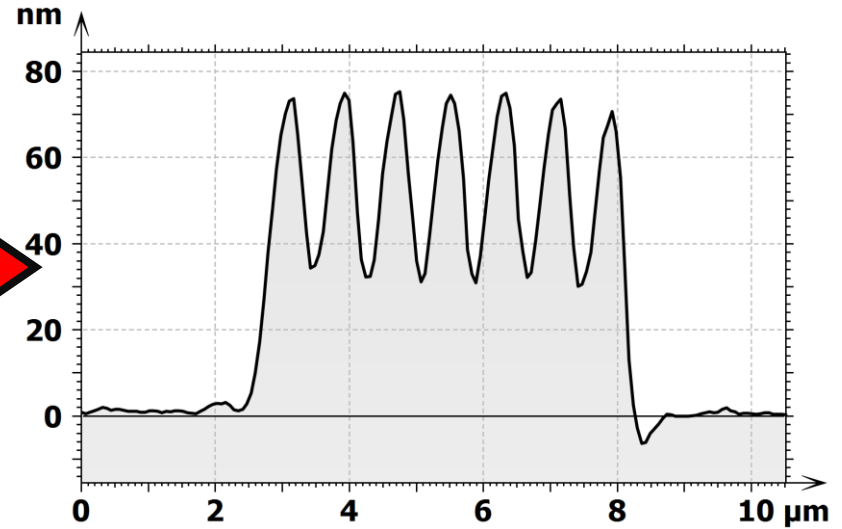
advanced data processing with super resolution

color coded 3d plot



noise reduction, increased resolution

profile

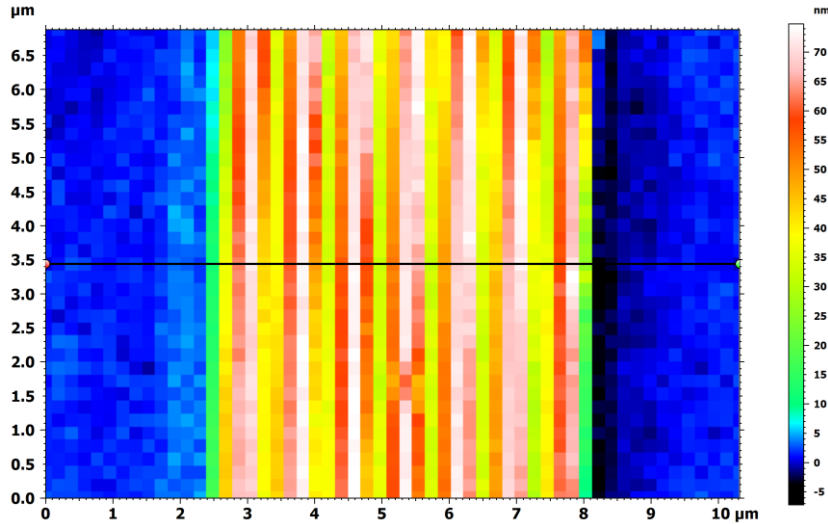


improved height signal



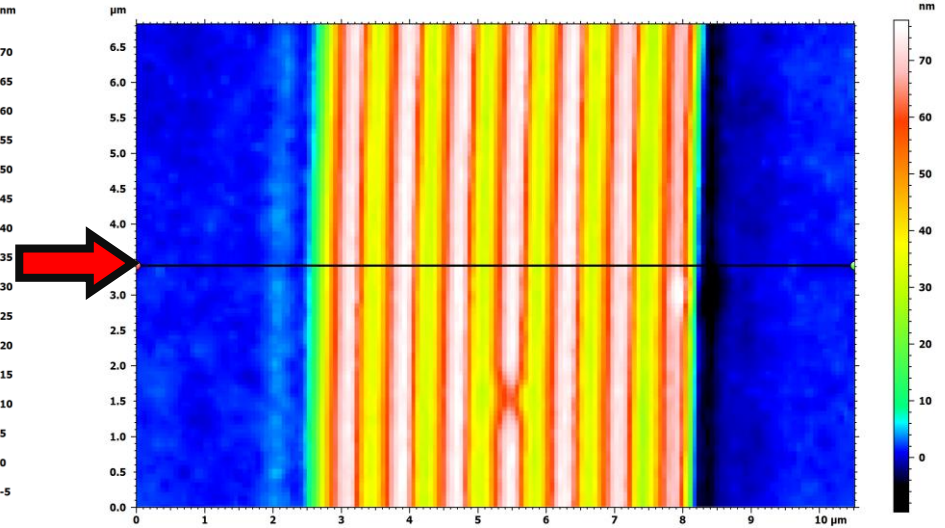
comparison of the 3d data

standard resolution



moiré effects, zones with reduced amplitude

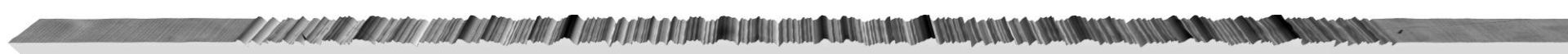
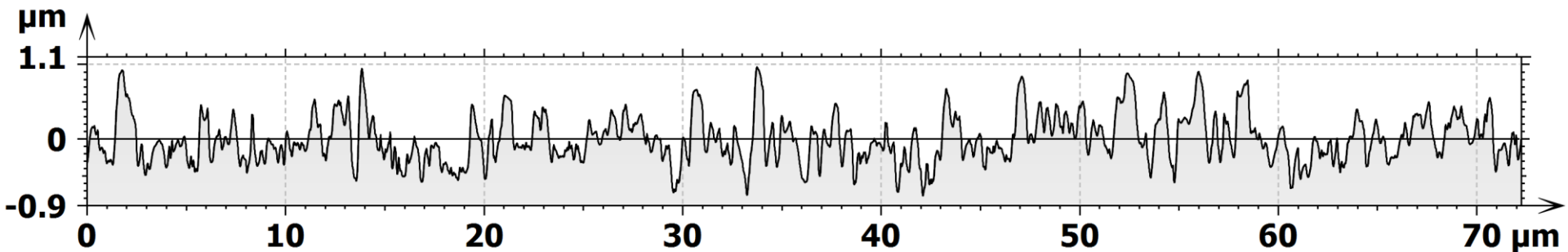
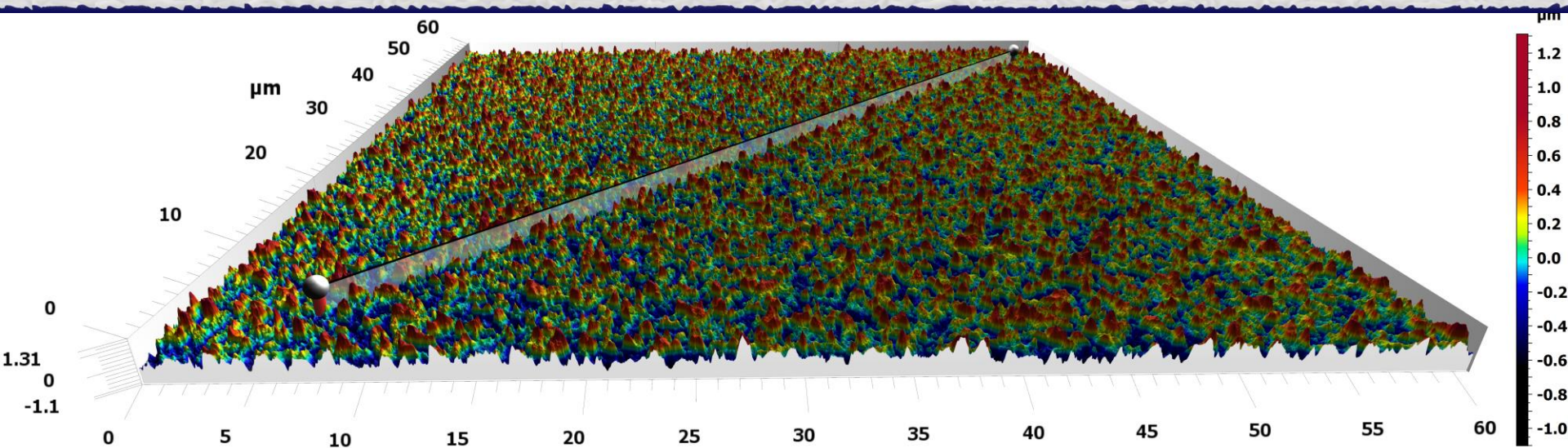
super resolution



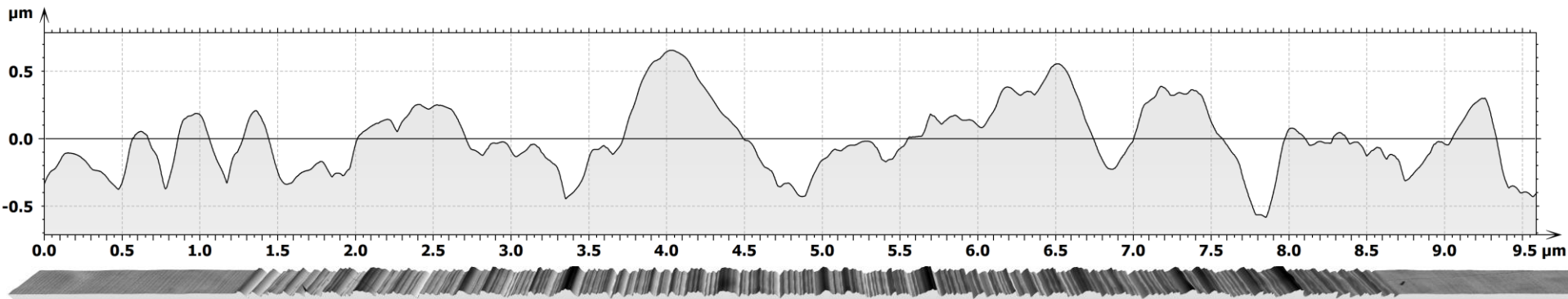
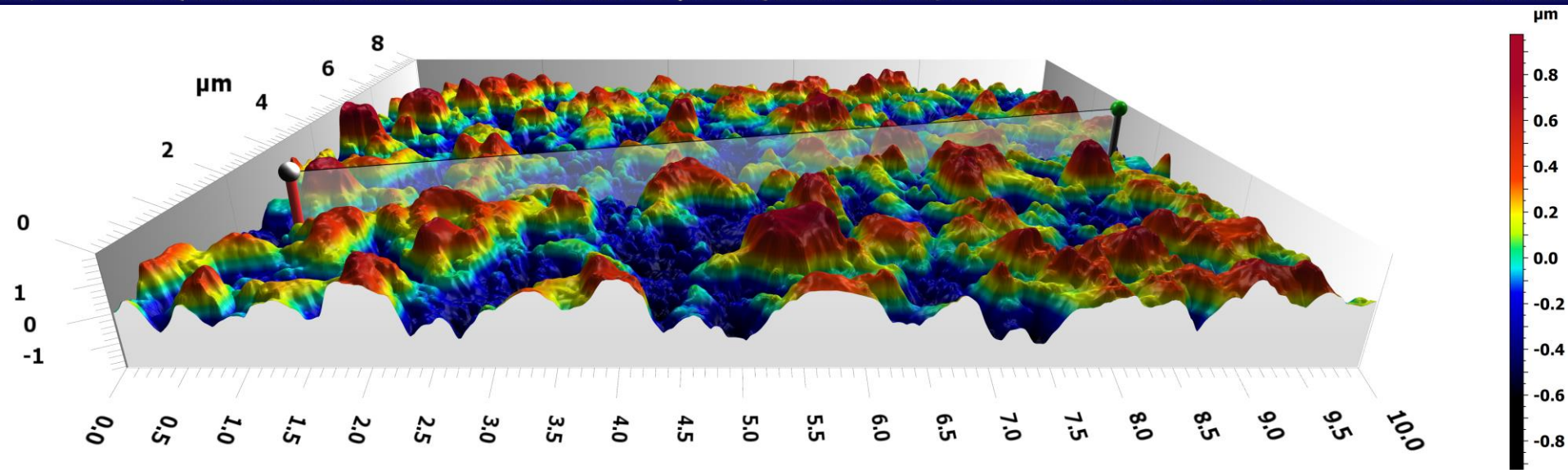
significant closer to the real 3d structures



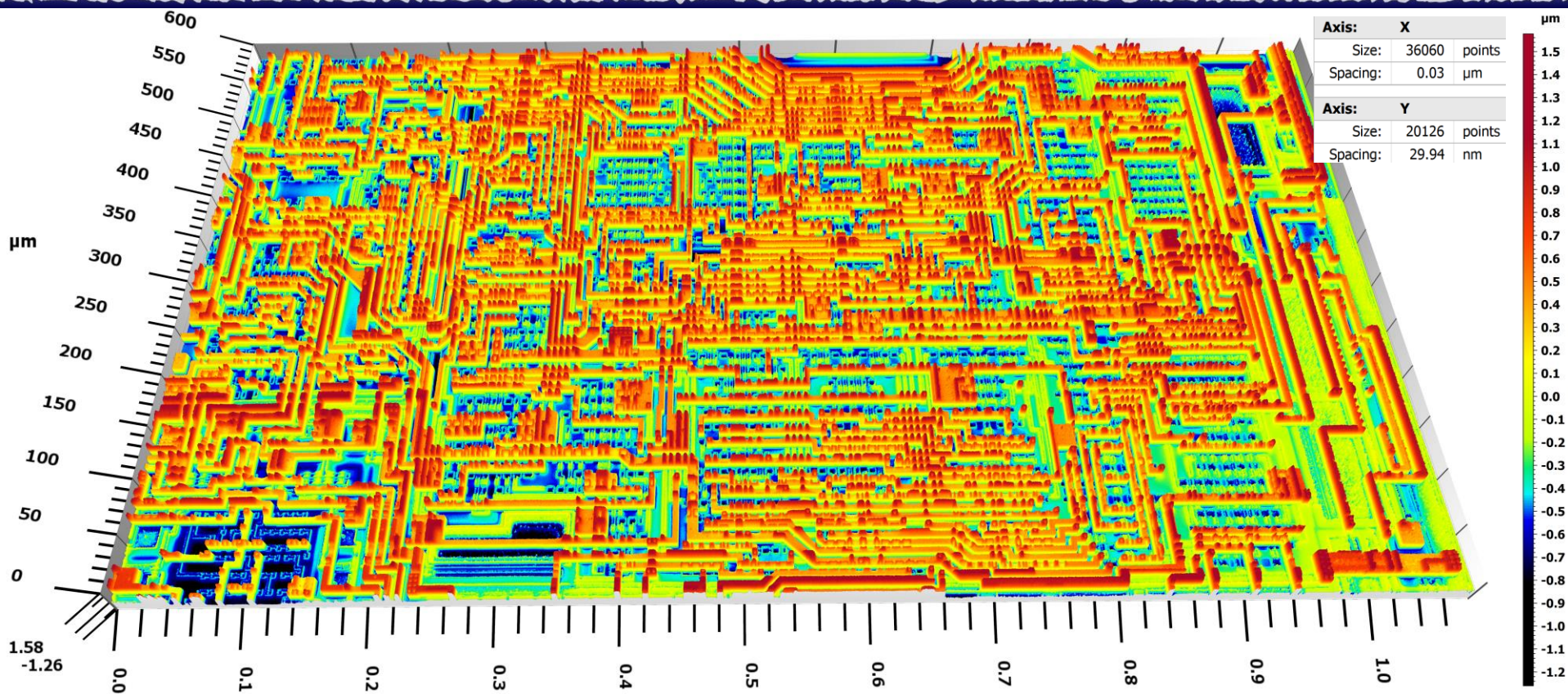
smartWLI nanoscan: “black silicon” structures



“black silicon” structures – partial area



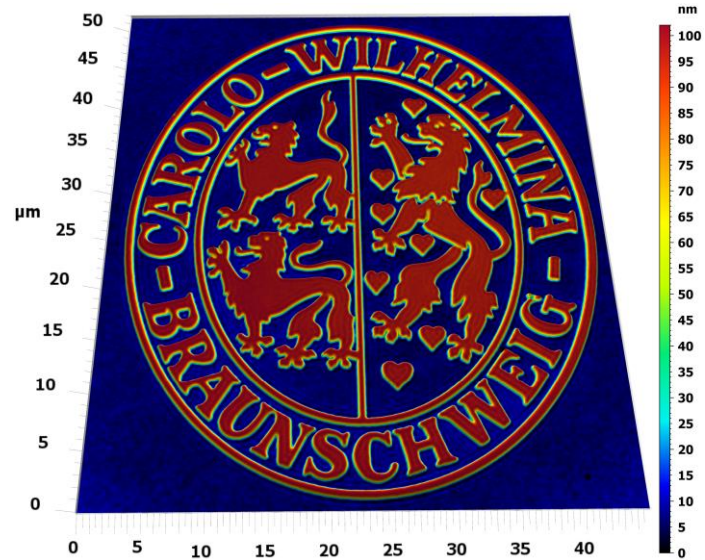
more details in a shorter measuring time



smartWLI nanoscan, 115x objective: 180 single scans, 10 min.

- *the systems can be used to measure functional surfaces with a size below 1 μm*
- *the algorithms used for the data evaluation have a strong influence to the practical achieved lateral resolution*
- *super resolution can improve the measuring results even if the original measuring point density of the camera is already significant below the optical resolution of the used objective*
- *structured height, material and geometry have a significant influence of the lateral resolution which the system can achieve*
- *the D_{LIM} parameter is a suitable tool to check the lateral resolution of the system*

Thank you for the support!



I would like to thank Mr. Machleidt and Mr. Schneider for the direct support with this presentation as well as all the other colleagues for the hard work which was necessary to get improve the performance of our systems to make presentation of such results possible.

The sinus structures from the PTB are a great help for resolution tests and further improvements. My greetings to Braunschweig! Last but not least I would like to thank for the support of the TU Ilmenau giving us a better understanding of such surfaces and SEM reference data.